

DECO 18 2002
AUG 2002
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

KIRIMURA et al.

Art Unit: 1765

Application No.: 09/822,414

Examiner: M. Song

Filed: April 2, 2001

Attorney Dkt. No.: 107351-00011

For: FILM FORMING APPARATUS AND METHOD OF FORMING A CRYSTALLINE
SILICON FILM

RECEIVED

DEC 20 2002

Commissioner for Patents
Washington, D.C. 20231

December 18, 2002

TC 1700

AMENDMENT

Sir:

In reply to the outstanding Office Action dated September 18, 2002, please amend the application as follows:

IN THE CLAIMS:

Please amend claims 16, 17 and 30 as follows:

16. (Amended) A crystalline silicon film forming method comprising the steps of:

preparing a film forming apparatus having a single silicon film forming vacuum chamber for forming a crystalline silicon film on a substrate, and provided with a film forming device for forming a pre-film of the crystalline silicon film on a target surface of said substrate, and an energy beam irradiating device for irradiating said pre-film with an energy beam for crystallizing said pre-film;